

FIG. 1A

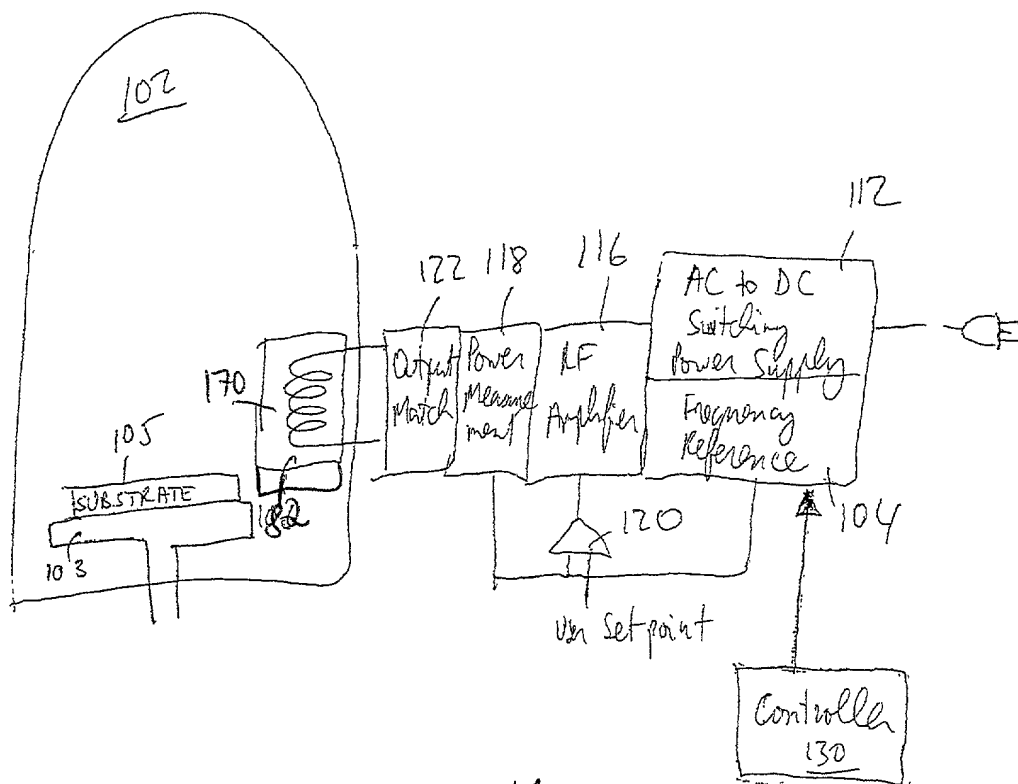


FIG. 1A

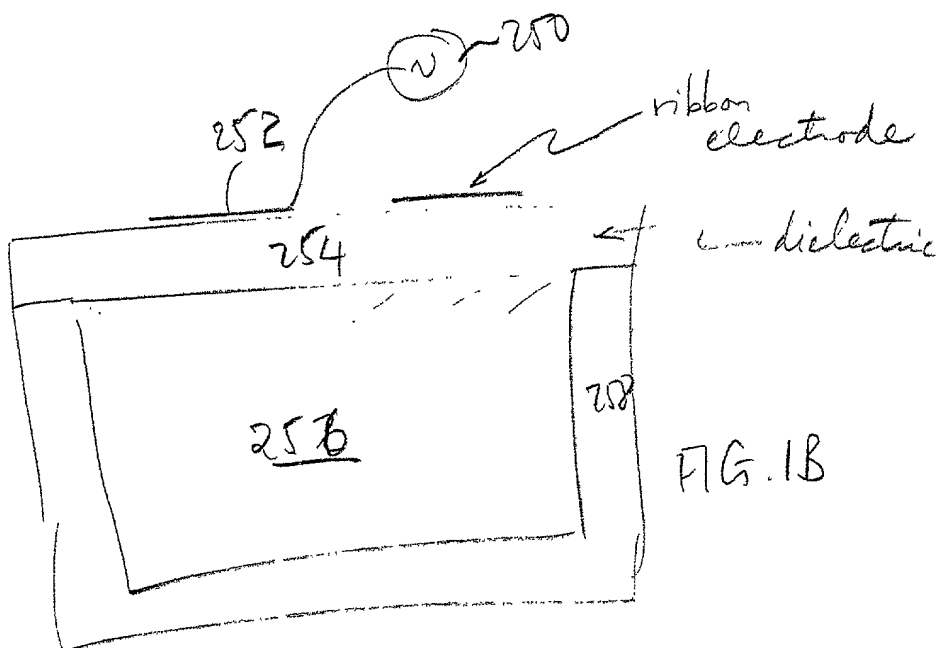


FIG. 1B

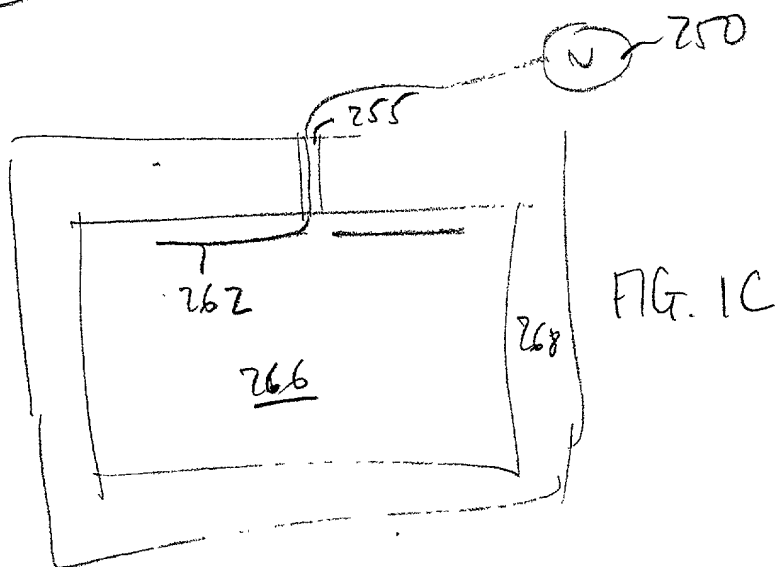


FIG. 1C

FIG. 1D

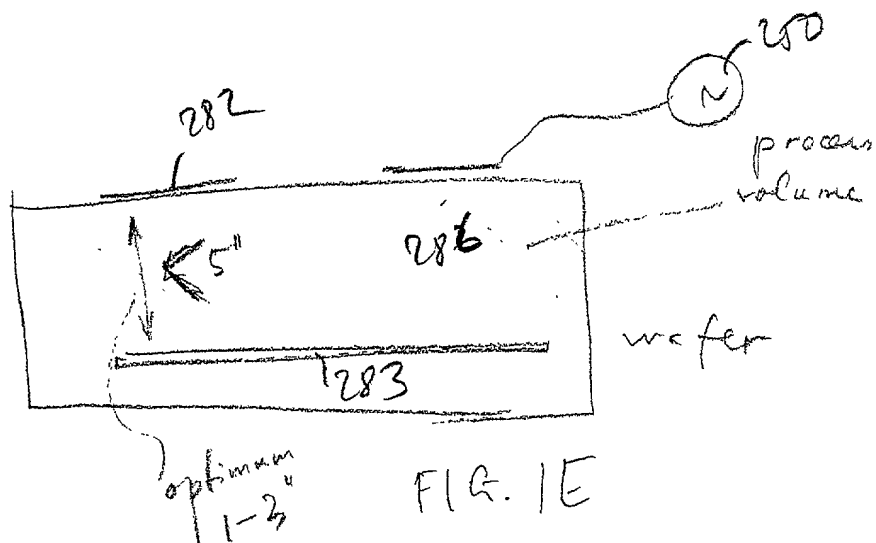
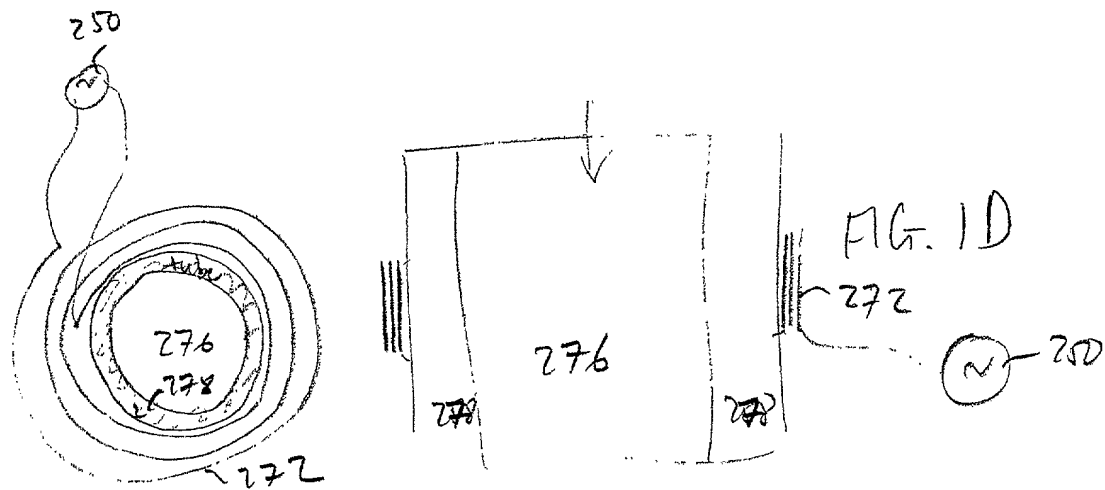


FIG. 2A

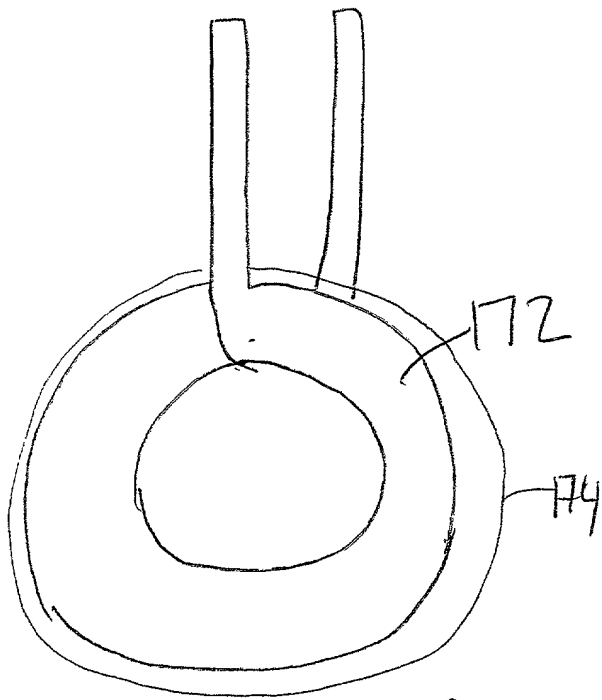
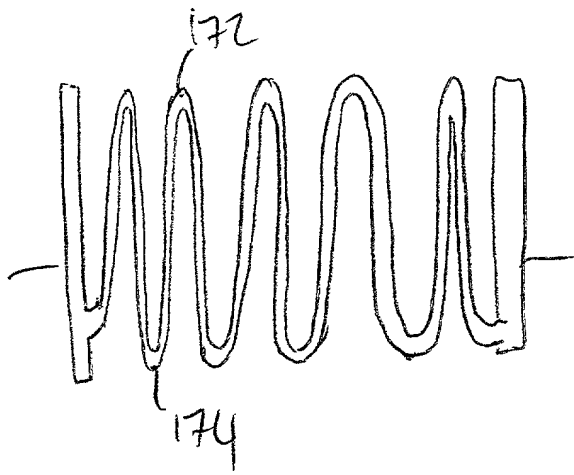


FIG. 2B

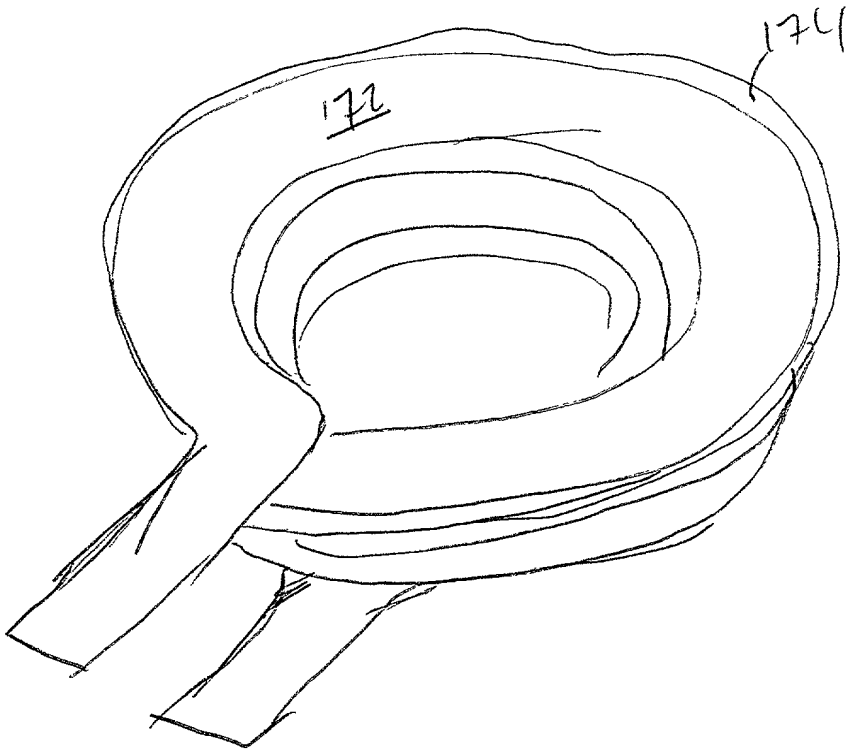


FIG. 2C

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graph TD
    200[Position Wafer in chamber 200] --> 202[Introduce Processing gas 202]
    202 --> 204[Pulse plasma generation 204]
    204 --> 206[Purge Gas 206]
    206 --> 208[Introduce Processing Gas 208]
    208 --> 210[Pulse plasma Generation 210]
    210 --> 212[Purge Gas 212]
    212 --> D{DONE?}
    D -- Y --> STOP([STOP])
    D -- N --> 208
  
```

FIG. 3

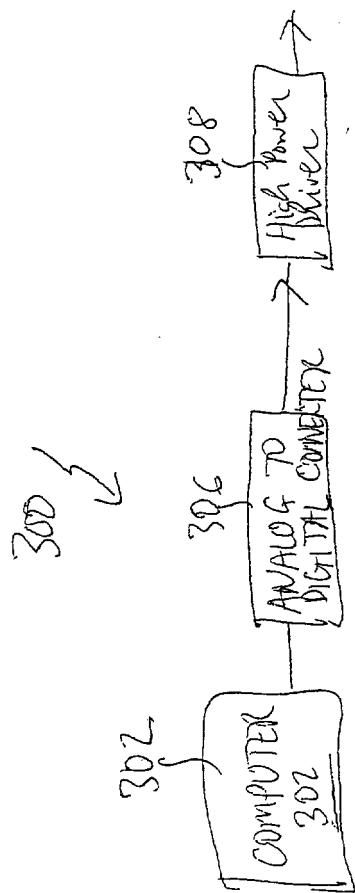


FIG. 4A

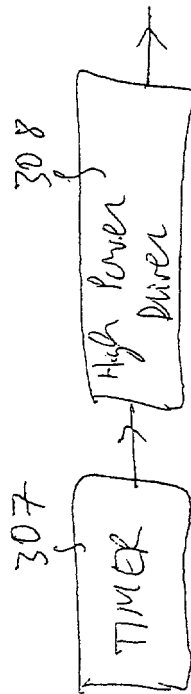


FIG. 4B

FIG. 5

800

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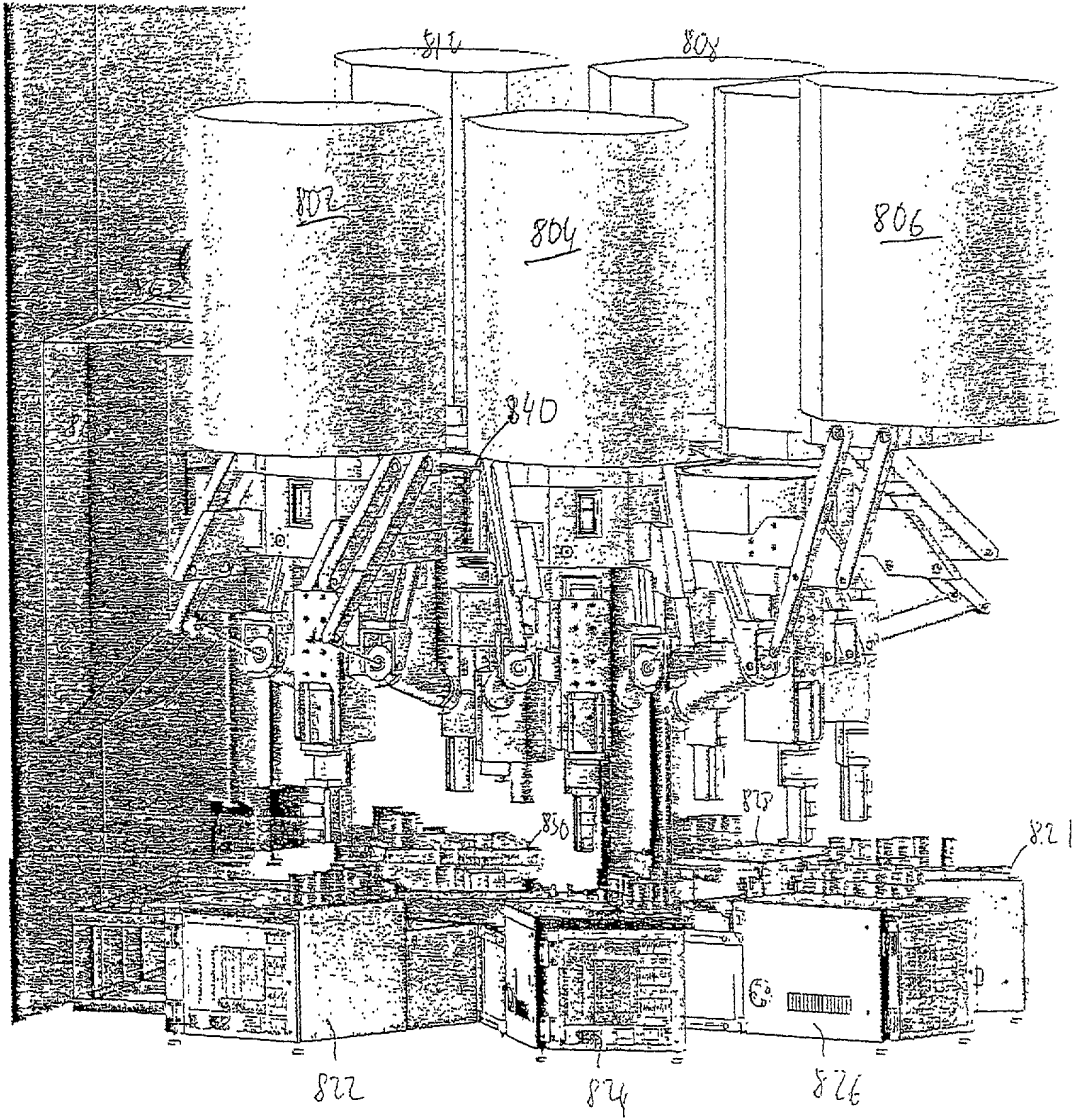


FIG. 5

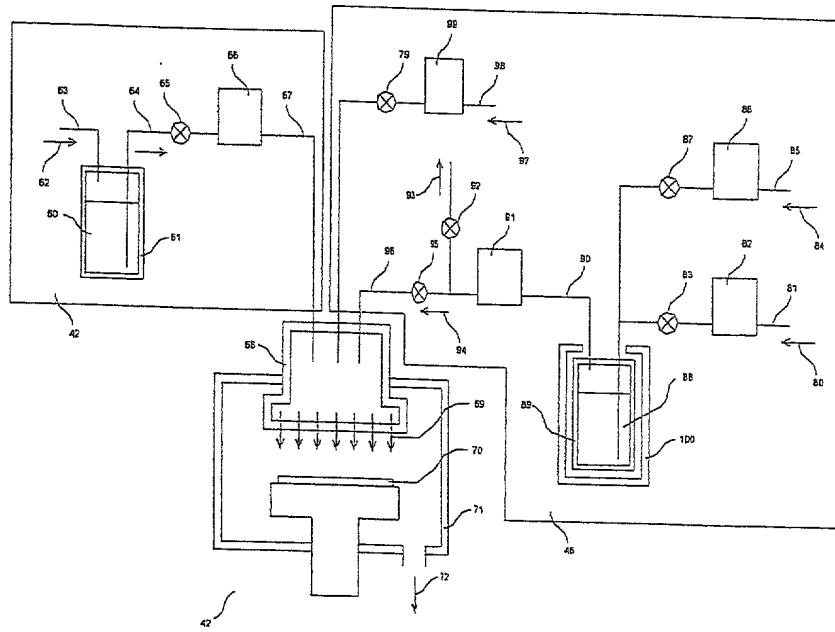


FIG. 6

